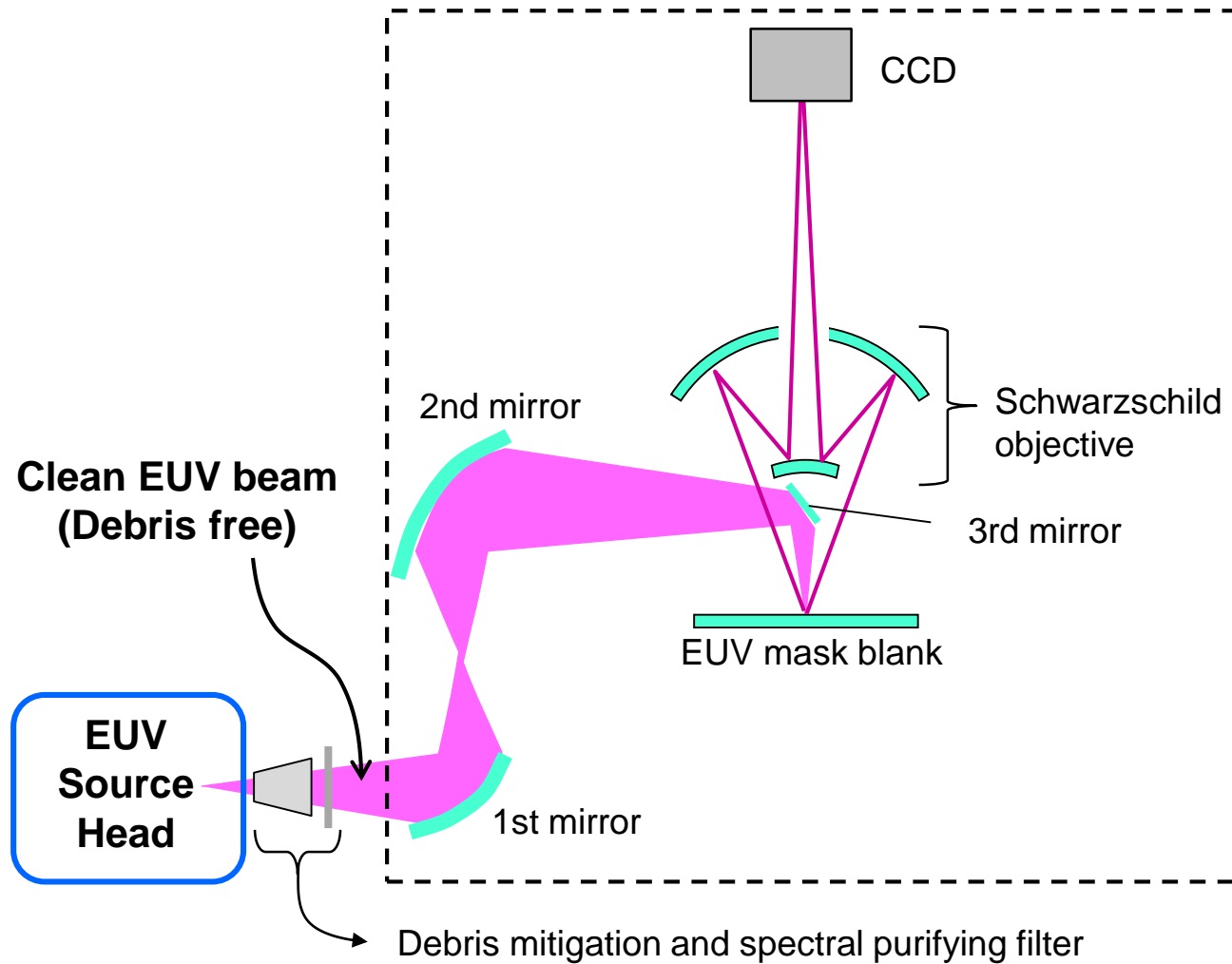


EUV source requirements for next generation ABI tools



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1. Etendue of the extracted EUV beam : $\sim 0.02 \text{mm}^2 \cdot \text{sr}$
2. Brightness of the in-band (13.5nm +/-1%) EUV beam after debris mitigation and spectral purifying filter $> 30 \text{W} / \text{mm}^2 \cdot \text{sr}$
3. 10ms integrated energy stability $< 1\%$ for > 1 hour
4. Continuous operation without any maintenance > 14 days
5. Downtime for a periodical maintenance of a source head < 6 hours